

## REVERSE TONE PROCESS FOR MASKS

### ABSTRACT OF THE DISCLOSURE

5           A reverse image mask is produced by initially depositing a metallic layer on a substrate. Resist is applied to the metallic layer to pattern desired features. The metallic layer is plated with a metal film, and the resist is then stripped. The metallic layer is etched using the metal film as a mask. Finally, the metal film is etched leaving the metallic layer etched in patterned areas to provide the reverse image mask.

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